Presentation M–4

Comprehensive Optimization of Cleaner Concentration Settings of Cleaning Operations in Electroplating Plants

H.H. Lou & Y.L. Huang,
Department of Chemical Engineering & Materials Science,
Wayne State University, Detroit, MI

Cleaning operations in electroplating plants consume huge amounts of cleaners. It is recognized that cleaner concentration settings in soaking, electrocleaning and acid cleaning are always very conservative. This has been a main cause of waste generation in wastewater as well as unreasonably high cleaner consumption. In this paper, a systematic optimization approach is introduced to identify optimal settings for different cleaning operations. The approach is general systematic and easy to use. A case study is given to demonstrate its applicability in real process systems.

Paper not available.

For more information, contact:
Y.L. Huang
Department of Chemical Engineering
& Materials Science
Wayne State University
Detroit, MI 48202
Phone: 313/577-3771
FAX: 313/577-3810